

What is claimed is:

1. A thermally developable light-sensitive material comprising a support having thereon light-sensitive silver halide grains, an organic silver halide salt and a reducing agent,

wherein when a regression line is obtained by plotting color coordinates (u^* , v^*) of the thermally developable light-sensitive material at optical densities of 0.5, 1.0, 1.5 and the minimum density on a two dimensional coordinates of CIE 1976 (L^* u^* v^*) color space, in which the abscissa is u^* and the ordinate is v^* ,

a coefficient of determination R^2 of the regression line is from 0.998 to 1.000.

2. The thermally developable light-sensitive material of claim 1, wherein v^* value of the regression line is within a range of -5 to 5 when u^* is 0.

3. The thermally developable light-sensitive material of claim 1, wherein the regression line has a gradient (u^* / v^*) of 0.7 to 2.5.

4. A thermally developable light-sensitive material comprising a support having thereon light-sensitive silver halide grains, an organic silver halide salt and a reducing agent,

wherein when a regression line is obtained by plotting color coordinates (a^* , b^*) of the thermally developable light-sensitive material at optical densities of 0.5, 1.0, 1.5 and the minimum density on a two dimensional coordinates of CIE 1976 (L^* a^* b^*) color space, in which the abscissa is a^* and the ordinate is b^* ,

a coefficient of determination R^2 of the regression line is from 0.998 to 1.000.

5. The thermally developable light-sensitive material of claim 4, wherein b^* value of the regression line is within a range of -5 to 5 when a^* is 0.

6. The thermally developable light-sensitive material of claim 4, wherein the regression line has a gradient (a^* / b^*) of 0.7 to 2.5.

7. A thermally developable light-sensitive material comprising a support having thereon light-sensitive silver halide grains, an organic silver halide salt and a reducing agent,

wherein when a regression line is obtained by plotting color coordinates (u^* , v^*) of the thermally developable light-sensitive material at optical densities of 0.5, 1.0 and 1.5 on a two dimensional coordinates of CIE 1976 (L^* u^* v^*)

color space, in which the abscissa is u^* and the ordinate is v^* ,

a coefficient of determination R^2 of the regression line is from 0.998 to 1.000.

8. The thermally developable light-sensitive material of claim 7, wherein v^* value of the regression line is within a range of -5 to 5 when u^* is 0.

9. The thermally developable light-sensitive material of claim 7, wherein the regression line has a gradient (u^* / v^*) of 0.7 to 2.5.

10. A thermally developable light-sensitive material comprising a support having thereon light-sensitive silver halide grains, an organic silver halide salt and a reducing agent,

wherein when a regression line is obtained by plotting color coordinates (a^* , b^*) of the thermally developable light-sensitive material at optical densities of 0.5, 1.0 and 1.5 on a two dimensional coordinates of CIE 1976 (L^* a^* b^*) color space, in which the abscissa is a^* and the ordinate is b^* ,

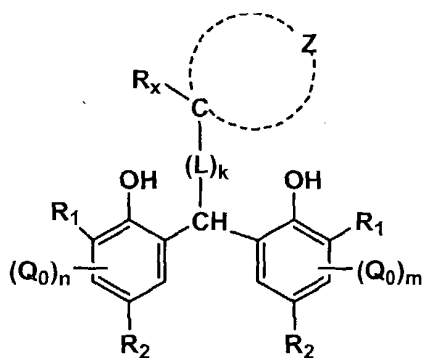
a coefficient of determination R^2 of the regression line is from 0.998 to 1.000.

11. The thermally developable light-sensitive material of claim 10, wherein b^* value of the regression line is within a range of -5 to 5 when a^* is 0.

12. The thermally developable light-sensitive material of claim 10, wherein the regression line has a gradient (a^* / b^*) of 0.7 to 2.5.

13. The thermally developable light-sensitive material of claim 1, comprising a reducing agent represented by following Formula (A-1) and a compound represented by following Formula (A-4),

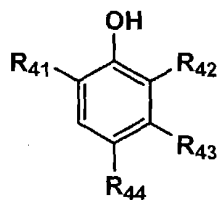
Formula (A-1)



wherein Z is a group of atoms necessary for forming a 3- through 10-membered ring together with the carbon atom; R_x is a hydrogen atom, an alkyl group, an alkenyl group or alkynyl group; R_1 , R_2 and Q_0 are each a group capable of substituting on the benzene ring; L is divalent linking group; k is an integer of 0 or 1; and n and m are each an

integer of 0 through 2; plural R_1 , R_2 and Q_0 each may be the same or different,

Formula (A-4)

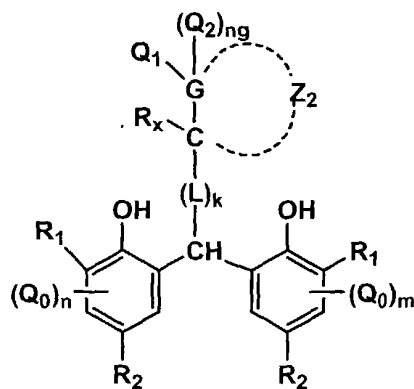


wherein R_{41} is a substituted or unsubstituted alkyl group; R_{42} is a hydrogen atom, a substituted or unsubstituted alkyl group or a substituted or unsubstituted acylamino group provided that R_{41} and R_{42} are not a 2-hydroxyphenylmethyl group; R_{43} is a hydrogen atom of a substituted or unsubstituted alkyl group; and R_{44} is a substituent capable of substituting on the benzene ring.

14. The thermally developable light-sensitive material of claim 13, wherein at least one of R_{41} and R_{42} is a divalent or trivalent alkyl group.

15. The thermally developable light-sensitive material of claim 13, wherein the reducing agent represented by Formula (A-1) is a reducing agent represented by following Formula (A-2),

Formula (A-2)



wherein Q_1 is a halogen atom, an alkyl group, an alkenyl group, an alkynyl group, an aryl group or a heterocyclic group; Q_2 is a hydrogen atom, a halogen atom, an alkyl group, an alkenyl group, an alkynyl group, an aryl group or a heterocyclic group; G is a nitrogen atom or a carbon atom that ng is 0 when G is the nitrogen atom and ng is 0 or 1 when the G is the oxygen atom; Z_2 is a group of atoms necessary for forming a 3- through 10-membered non-aromatic ring together with the carbon atom and G ; and R_1 , R_2 , R_x , Q_0 , L , k , n and m are each the same as those in Formula A-1.

16. The thermally developable light-sensitive material of claim 15, wherein the non-aromatic ring formed by Z_2 together with the carbon atom and G in Formula (A-2) is a 6-member non-aromatic ring.

17. The thermally developable light-sensitive material of claim 1, wherein the thermally developable light-sensitive material further comprises a silver saving agent selected from the group consisting of vinyl compounds, hydrazine derivatives, silane compounds and tetravalent onium salt on the silver halide grain side of the support.

18. An image forming method comprising the step of forming an image by developing the thermally developable light sensitive material described in claim 1 under a temperature of from 110 °C to 140 °C for a time of from 5 seconds to 20 seconds.

19. An image forming method comprising the step of forming an image by exposing the thermally developable light-sensitive material described in claim 1 with a laser having an wavelength of from 400 nm to 830 nm.

20. An image forming method comprising the step of forming an image by exposing the thermally developable light-sensitive material described in claim 1 with an laser having an wavelength of from 780 nm to 830 nm.